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This article [*J. Micro/Nanolith. MEMS MOEMS*, **12**(4), 041203 (2013)] was originally published online on 25 September 2013 with errors in Figure 6. The figure sequence in the caption did not match the sequence given in the figure.

Also, Fig. 6(d) showed an image of aluminum mask with a crossbar on the image which is not visible and an improper scale with a typographical error.

The corrected figure and caption appear below. Online versions were corrected on 08 January 2014.

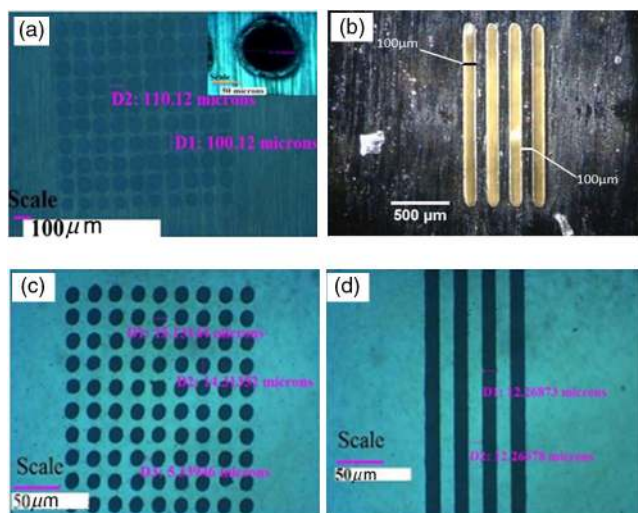


Fig. 6 Optical micrographs of enlarged aluminum mask manufactured through micromilling and drilling for (a) micropillar array (imaged at 4×) (magnified view of microdrilled area in callout), (b) microchannel array (imaged at 4×), and laser micromachined image on the chromated glass slide for (c) micropillar array (imaged at 4×) and (d) microchannel array (imaged at 4×).

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